What is claimed is

1. A process for the manufacture of a tetrazole of formula

or a tautomer or a salt thereof, wherein R represents an organic residue; comprising

- (i) reacting a compound of formula R-CN (II a) with an azide of formula (R_1)(R_2)M-N₃ (IIb), wherein R has the meaning as defined above; R_1 and R_2 , independently of another, represent an organic residue such as an aliphatic residue, an alicyclic residue, a heteroalicyclic residue; an alicyclic-aliphatic residue; a heteroalicyclic aliphatic residue; a carbocyclic or a heterocyclic aromatic residue; an araliphatic residue or an heteroaraliphatic residue, each residue, independently of another, being unsubstituted or substituted; and M is boron or aluminium; and
- (ii) isolating the resulting compound of formula (I).
- 2. A process according to claim 1 for the manufacture of said angiotensin II receptor antagonists having as structural feature a tetrazol ring, e.g. of formula (IV),

or a tautomeric form thereof, wherein Rx represents a structural element selected from the group consisting of

(derived from losartan - cf. EP 253310);

(derived from irbesartan - cf. EP 454511);

(derived from UR-7247);

(derived from candesartan-cilexetril- EP

459136);

or, in each case, a salt thereof; characterized by reacting a compound of formula (IV a)

wherein Rx has the meanings as given above,

with a compound of formula $(R_1)(R_2)M-N_3$ (II b), wherein R_1 and R_2 , independently of one another, represent an organic residue; and isolating the resulting compound of formula (IV).

3. A process according to claim 1 for the manufacture of a compound of formula (IV b) comprising reacting a compound of formula (IV c)

or an ester thereof with an azide of formula $(R_1)(R_2)M-N_3$ (IIb), wherein R_1 and R_2 , independently of each other, have the meanings as defined above, and isolating the compound of formula (IV b).

4. A process according to claim 1 for the manufacture of a compound of formula manufacture of a compound of formula

a tautomeric form thereof wherein Ry represents C_1 - C_8 -alkyl such as methyl; C_1 - C_8 -alkyl substituted by X' and X' being halogen, sulphonyloxy, hydroxyl, protected hydroxyl, such as bromomethyl, or an acetal of formyl; and X_1 being in a benzylic position, comprising reacting a compound of formula (IV a)

with a compound of formula $(R_1)(R_2)M-N_3$ (II b), wherein R_1 and R_2 , independently of one another, represent an organic residue; and isolating the resulting compound of formula (V).

5. A process for the manufacture of the compound of formula (VI)

or a tautomer or salt thereof, comprising

(a) treating a compound of formula (VI a)

wherein X represents a leaving group, first with a nucleophilic agent and then with a "solvolytic" base resulting in a compound of formula (VI b)

(b) reacting a compound of formula (V b) with an azide of formula $(R_1)(R_2)M-N_3$ (II b), wherein the variables R_1 and R_2 , independently of one another, have the meanings as defined above; resulting in a compound of formula (VI c)

(VI c) or a tautomer or salt thereof

(c) oxidizing a compound of formula (VI c) or a tautomer or salt thereof resulting in a compound of formula (VI)

or a tautomer or salt thereof; and

- (d) isolating the compound of formula (VI) or a tautomer or salt thereof.
- 6. A process for the manufacture of a compound of formula (V d)

comprising oxidizing a compound of formula (VI c)

or a tautomer or salt thereof resulting in a compound of formula (VI) or a tautomer or salt thereof; and isolating a resulting compound of formula (VI).

- 7. A process according to claim 5 or 6, wherein the oxidation is carried out in the presence of an oxidation agent selected from the group consisting of HNO₂, HNO₃ or a corresponding anhydride thereof, and a peroxodisulfate, and wherein as solvent an alkylated aromatic hydrocarbon solvent such as toluene is used.
- 8. A process according to claim 1 for the manufacture of a compound of formula

a tautomeric form thereof, wherein Ry represents C_1 - C_8 -alkyl such as methyl; C_1 - C_8 -alkyl substituted by X' and X' being halogen, sulphonyloxy, hydroxyl, protected hydroxyl, such as bromomethyl, formyl or an acetal thereof; comprising reacting a compound of formula (VII a)

with a compound of formula $(R_1)(R_2)M-N_3$ (II b), wherein R_1 and R_2 , independently of one another, represent an organic residue; and isolating the resulting compound of formula (VI).

- 9. A process according to any one of claims 1 to 5 and 8, wherein a compound of formula $(R_1)(R_2)M-N_3$ (II b) is used, wherein M is aluminium or boron; and R_1 and R_2 , independently of one another, is C_1-C_8 -alkyl such as methyl, ethyl, propyl, diisobutyl, tert-butyl or n-octyl; C_3-C_7 -alkenyl such as allyl or crotyl, C_3-C_7 -cycloalkyl such as cyclohexyl; phenyl- C_1-C_4 -alkyl such as benzyl or 2-phenethyl; phenyl- C_3-C_5 alkenyl such as cinnamyl, or C_3-C_8 -cycloalkyl- C_1-C_8 -alkyl such as cyclopropylmethyl or cyclohexylmethyl.
- 10. A compound of formula $(R_1)(R_2)M-N_3$ (II b), wherein M is aluminium or boron; and R_1 and R_2 , independently of one another, is C_3-C_7 -alkenyl such as allyl or crotyl, C_3-C_7 -cycloalkyl such as cyclohexyl; phenyl- C_1-C_4 -alkyl such as benzyl or 2-phenethyl; phenyl- C_3-C_5 alkenyl such as cinnamyl, or C_3-C_8 -cycloalkyl- C_1-C_8 -alkyl such as cyclopropylmethyl or cyclohexylmethyl.